Ref #	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
S1	2	"20030063266"	US-PGPUB; USPAT; DERWENT	OR	ON	2005/06/10 09:15
S2	2	"6741329".pn.	US-PGPUB; USPAT; DERWENT	OR	ON	2005/06/10 09:21
S3	1	"5437946".PN.	USPAT; USOCR	OR	ON	2005/06/10 09:16
S4	1	"6013401".PN.	USPAT; USOCR	OR	ON	2005/06/10 09:16
S5	1	"6081319".PN.	USPAT; USOCR	OR	ON	2005/06/10 09:17
S6	182377	(radiation or light or beam) near4 (adjust$4 or attenuat$3 or uniform$3 or homogen$5)	US-PGPUB; USPAT; DERWENT	OR	ON	2005/06/10 11:00
S7	134	S6 and (two or first or second) near3 sheet same electr$5 near3 conduct$3	US-PGPUB; USPAT; DERWENT	OR	ON	2005/06/10 13:09
S8	24604	S6 and (lithograph$2 or photolithograph$2 or microlithograph$2 or (expos$3 or pattern$3) near4 (wafer or substrate))	US-PGPUB; USPAT; DERWENT	OR	ON	2005/06/10 10:20
S9	7987	S6 and imag$3 near4 (wafer or substrate)	US-PGPUB; USPAT; DERWENT	OR	ON	2005/06/10 09:28
S10	26635	(S8 or S9)	US-PGPUB; USPAT; DERWENT	OR	ON	2005/06/10 09:28
S11	21670	(adjust$4 or attenuat$3 or uniform$3 or homogen$5) same (two or first or second) near3 (sheet or plate) same (connect$3 or fasten$3 or join$3 or attach$3)	US-PGPUB; USPAT; DERWENT	OR	ON	2005/06/10 09:31
S12	208	S10 and S11	US-PGPUB; USPAT; DERWENT	OR	ON	2005/06/10 09:50
S13	2	S12 and 355/71.ccls.	US-PGPUB; USPAT; DERWENT	OR	ON	2005/06/10 09:52
S14	1471	355/71.ccls.	US-PGPUB; USPAT; DERWENT	OR	ON	2005/06/10 09:53
S15	682	S6 and S14	US-PGPUB; USPAT; DERWENT	OR	ON	2005/06/10 10:19

S16	273817	(attenuator or attenuating or corrector or correcting)	US-PGPUB; USPAT; DERWENT	OR	ON	2005/06/10 10:20
S17	15235	S16 and (lithograph$2 or photolithograph$2 or microlithograph$2 or (expos$3 or pattern$3) near4 (wafer or substrate))	US-PGPUB; USPAT; DERWENT	OR	ON	2005/06/10 11:01
S18	186	S14 and S17	US-PGPUB; USPAT; DERWENT	OR	ON	2005/06/10 10:21
S19	33524	(radiation or light or beam) near4 (adjust$4 or attenuat$3 or uniform$3 or homogen$5) same intensity	US-PGPUB; USPAT; DERWENT	OR	ON	2005/06/10 13:24
S20	6774	S19 and (lithograph$2 or photolithograph$2 or microlithograph$2 or (expos$3 or pattern$3 or imag$3) near5 (wafer or substrate))	US-PGPUB; USPAT; DERWENT	OR	ON	2005/06/10 12:25
S21	283350	(adjust$4 or attenuat$3 or uniform$3 or homogen$5) same (rod or (sheet or plate) same (actuat$3 or control$4 or electric$4))	US-PGPUB; USPAT; DERWENT	OR	ON	2005/06/10 13:06
S22	1240	S20 and S21	US-PGPUB; USPAT; DERWENT	OR	ON	2005/06/10 11:05
S23	303	S22 and (355/53,67,71.ccls. or 430/30,311.ccls. or 250/548,492. 1.ccls.)	US-PGPUB; USPAT; DERWENT	OR	ON	2005/06/10 12:13
S24	1	"4390789".PN.	USPAT; USOCR	OR	ON	2005/06/10 11:57
S25	1	"5144142".PN.	USPAT; USOCR	OR	ON	2005/06/10 11:57
S26	1	"5892224".PN.	USPAT; USOCR	OR	ON	2005/06/10 11:58
S27	1	"6145438".PN.	USPAT; USOCR	OR	ON	2005/06/10 12:00
S28	1	"6483120".PN.	USPAT; USOCR	OR	ON	2005/06/10 12:00
S29	1	"6515409".PN.	USPAT; USOCR	OR	ON	2005/06/10 12:00

S30	31	("5724122" or "6307619" or "4589769" or "5390227" or "5889758" or "5600698" or "5512759" or "6404499" or "6438199" or "6573978" or "5339346" or "6225027").pn. or "2004007922" or "2004027922"	US-PGPUB; USPAT; DERWENT	OR	ON	2005/06/10 12:15
S31	7793	(radiation or light or beam) near4 (adjust$4 or attenuat$3 or uniform$3 or homogen$5) same intensity	EPO; JPO; DERWENT	OR	ON	2005/06/10 12:24
S32	318	S31 and (lithograph$2 or photolithograph$2 or microlithograph$2 or (expos$3 or pattern$3 or imag$3) near5 (wafer or substrate))	EPO; JPO; DERWENT	OR	ON	2005/06/10 13:26
S33	12	S32 and asml.asn.	EPO; JPO; DERWENT	OR	ON	2005/06/10 12:40
S34	1087	asml.asn.	EPO; DERWENT	OR	ON	2005/06/10 12:41
S35	3548	S19 and "359"/$.ccls.	US-PGPUB; USPAT; DERWENT	OR	ON	2005/06/10 13:04
S36	599	S35 and (adjust$4 or attenuat$3 or uniform$3 or homogen$5) same (rod or (sheet or plate) same (actuat$3 or control$4 or electric$4))	US-PGPUB; USPAT; DERWENT	OR	ON	2005/06/10 13:06
S37	126	S36 and (sheet or plate) near4 (joined or connect$3 or combined or fastened or attached or bonded or bound)	US-PGPUB; USPAT; DERWENT	OR	ON	2005/06/10 13:10
S38	4345	(homogen$6 or attenuator or attenuating) near4 (radiation or light or beam).clm,ti.	US-PGPUB; USPAT; DERWENT	OR	ON	2005/06/10 13:30
S39	709	S38 and (lithograph$2 or photolithograph$2 or microlithograph$2 or (expos$3 or pattern$3 or imag$3) near5 (wafer or substrate))	US-PGPUB; USPAT; DERWENT	OR	ON	2005/06/10 13:26
S40	4358	(homogen$6 or attenuator or attenuating) near4 (radiation or light or beam) same (filter or rods or (sheet or plate) or ribbon same wire)	US-PGPUB; USPAT; DERWENT	OR	ON	2005/06/10 13:32
S41	222	S39 and S40	US-PGPUB; USPAT; DERWENT	OR	ON	2005/06/10 13:32

S42	9	("6169624" or "6856630").pn. or ep-1202101-$.did. or ep-1109067-$.did. or ep-1026547-$.did. or ep-939341-$.did. or de-19935568-$.did.	US-PGPUB; USPAT; DERWENT	OR	ON	2005/06/10 14:06